

Substitute Form PTO-1449 (Modified)		U.S. Department of Commerce Patent and Trademark Office	Attorney's Docket No. 18239-023US1	Application No. 10/597,806
Information Disclosure Statement by Applicant (Use several sheets if necessary)		Applicant Bernhard Kneer et al.		
(37 CFR §1.98(b))		Filing Date August 8, 2006	Group Art Unit 3722	

U.S. Patent Documents

Examiner Initial	Desig. ID	Document Number	Publication Date	Patentee	Class	Subclass	Filing Date If Appropriate
	AA	2005/0248856	11/2005	Omura et al.			
	AB	2003/174408	9/8/2003	Rostalski Hans-Juergen et al.			
	AC	2004/0109237	6/10/2004	Epple et al.			
	AD	2007/0052936	3/8/2007	Philips			
	AE	2005/024609	2/3/2005	De Smit et al.			
	AF	2005/0219707	10/6/2005	Schuster et al.			
	AG	2005/0225737	10/13/2005	Weisseneder et al.			
	AH	2006/0221582	10/5/2006	DeNies et al.			
	AI	2005/0190455	9/1/2005	Rostalski et al.			
	AJ	2005/0179877	8/18/2005	Mulkens et al.			
	AK	2003/0174408	9/18/2003	Rostalski et al.			
	AL	2005/0161644	7/28/2005	Zhang et al.			
	AM	2005/0117224	6/2/2005	Shafer et al.			
	AN	2005/074704	4/7/2005	Endo et al.			
	AO	2005/0068499	3/31/2005	Docdoc et al.			
	AP	2005/0024609	2/3/2005	De Smit et al.			
	AQ	4,346,164	8/24/1982	Tabarelli et al.			
	AR	4,890,903	1/2/1990	Treisman et al.			
	AS	5,682,263	10/1997	Robb et al.			
	AT	6,181,485	1/2001	He, Chuan			
	AU	2005/0074704	4/7/2005	Endo et al.			
	AV	2006/0187430	8/24/2006	Docdoc et al.			
	AW	2005/074704	4/7/2005	Endo et al.			
	AX	2005/0179877	8/18/2005	Mulkens et al.			
	AY	2005/0219707	10/6/2005	Schuster et al.			
	AZ	6,809,794	10/26/2004	Sewell			
	AAA	2004/075895	04/22/2004	Jeng et al.			

Examiner Signature	/Mesfin Asfaw/	Date Considered	10/24/2008
EXAMINER: Initials citation considered. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.			

ALL REFERENCES CONSIDERED EXCEPT WHERE LINED THROUGH. /M.A./

Substitute Form PTO-1449 (Modified)	U.S. Department of Commerce Patent and Trademark Office	Attorney's Docket No. 18239-023US1	Application No. 10/597,806
Information Disclosure Statement by Applicant (Use several sheets if necessary)		Applicant Bernhard Kneer et al.	
		Filing Date August 8, 2006	Group Art Unit 3722
(37 CFR §1.98(b))			

U.S. Patent Documents							
Examiner Initial	Desig. ID	Document Number	Publication Date	Patentee	Class	Subclass	Filing Date If Appropriate
	ABB	5,900,354	05/04/1999	Batchelder et al.			
	ACC	7,187,503	03/06/2007	Rostalski et al.			
	ADD	2006/0012885	01/19/2006	Beder et al.			
	AEE	2007/0091451	04/26/2007	Schuster			
	AFF	2007/0109659	05/17/2007	Rostalski et al.			
	AGG	2006/0221456	10/05/2006	Shafer et al.			
	AHH	2005/0225737	10/13/2005	Weissenrieder et al.			
	AII	2006/0244938	11/02/2006	Schuster			
	AJJ	2006/0066962	03/30/06	Totzeck et al.			
	AKK	2005/0190435	09/01/2005	Shafer et al.			

Foreign Patent Documents or Published Foreign Patent Applications							
Examiner Initial	Desig. ID	Document Number	Publication Date	Country or Patent Office	Class	Subclass	Translation
							Yes No
ALL	EP0291596		1/19/1994	EPO			
AMM	WO 2005/059617		6/30/2005	WIPO			
ANN	WO 2006/045748		5/4/2006	WIPO			
AOO	WO 2005/006026		1/20/2005	WIPO			
APP	WO 2005/081067		9/1/2005	WIPO			
AQQ	WO 2005/059645		6/30/2005	WIPO			
ARR	WO 2005/059618		6/30/2005	WIPO			
ASS	WO 2004/019128		3/4/2004	WIPO			
ATT	WO 2005/031823		4/7/2005	WIPO			
AUU	EP 1522894		4/13/2005	EPO			
AVV	EP 1486827		12/15/2004	EPO			
AWW	EP 0023231		2/4/1981	EPO			
AXX	DD 221563		4/24/1985	Germany			
AYY	DD 224448		7/3/1985	Germany			

Examiner Signature /Mesfin Asfaw/	Date Considered 10/24/2008
EXAMINER: Initials citation considered. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.	

Substitute Form PTO-1449 (Modified)	U.S. Department of Commerce Patent and Trademark Office	Attorney's Docket No. 18239-023US1	Application No. 10/597,806
Information Disclosure Statement by Applicant (Use several sheets if necessary)		Applicant Bernhard Kneer et al.	
		Filing Date August 8, 2006	Group Art Unit 3722
(37 CFR §1.98(b))			

Foreign Patent Documents or Published Foreign Patent Applications

Examiner Initial	Desig. ID	Document Number	Publication Date	Country or Patent Office	Class	Subclass	Translation	
							Yes	No
AZZ	EP 1420302	5/19/2004	EPO					
AAAA	EP 1524558	4/20/2005	EPO					
BBBB	JP 07220990	8/18/1995	Japan					
ACCC	JP10-228661	8/25/1998	Japan					
ADDD	JP10-303114	11/13/1998	Japan					
AEEE	EP 1 645 911	04/12/2006	EPO					
AFFF	EP 1 557 721	07/25/2005	EPO					
AGGG	EP 1 489 462	12/22/2004	EPO					
AHHH	EP 1 630 616	03/01/2006	EPO					

Other Documents (include Author, Title, Date, and Place of Publication)

Examiner Initial	Desig. ID	Document
AIII		Burnett et al., "High Index Materials for 193 nm immersion Lithography", International Symposium on Immersion & 157 nm Lithography, February 8, 2004, pp 3, figure 1.
AJJJ		Damrel et al., "193 nm Immersion Lithography – Taking the Plunge", Journal of Photopolymer Science and Technology, vol. 17 no. 4, pp 587-607 (2004).
AKKK		Kawata et al., "Fabrication of 0.2mm Fine Patterns Using Optical Projection Lithography With an Oil Immersion Lens", Japanese Journal of Applied Physics, Japan Society of Applied Physics, Tokyo, Japan, vol. 31 no. 12B, Part 1, December 1, 1992, pp 4174-4177.
ALLL		Owa et al., "Immersion Lithography; its Potential Performance Issues", Proceeding of the SPIE, SPIE, Bellingham, VA, vol. 5040 no. 1, February 28, 2003, pp 724-733.
AMMM		J.A. Hoffnagle et al., "Liquid Immersion Deep-Ultraviolet Interferometric Lithography", Journal of Vacuum Science & Technology B: Microelectronics Processing and Phenomena, American Vacuum Society, New York, NY, Vol. 17, No. 6, November 1999 (199-11) pp 3306-3309.
ANNN		Smith, Bruce, "Water-based 193nm Immersion Lithography", Online!, http://www.sematech.org/resources/litho/meetings/immersion/20040128/presentations/06%20rit20%20microstepper%20effortsSmith.pdf , (January 28, 2004).

Examiner Signature	/Mesfin Asfaw/	Date Considered	10/24/2008
EXAMINER: Initials citation considered. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.			

ALL REFERENCES CONSIDERED EXCEPT WHERE LINED THROUGH. /M.A./